



JC02 Rec'd PCT/PTO 25 MAR 2005

PCT

PATENT

IN THE UNITED STATES PATENT
AND TRADEMARK OFFICE

Applicants: Gogolides et al.

Serial No.: 10/516,384

Filed: May 30, 2003

For: LITHOGRAPHIC
MATERIALS BASED ON
POLYMERS CONTAINING
POLYHEDRAL OLIGOMERIC
SILSESQUIOXANES

Group Art Unit: To be assigned

Examiner: To be assigned

I hereby certify that this paper is being
deposited with the United States Postal Service
as first class mail, postage prepaid, in an
envelope addressed to: Commissioner for
Patents, P.O. Box 1450, Alexandria, VA
22313-1450 on this date:

March 21, 2005

James P. Zeller

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The patents listed on the enclosed Form PTO-1449 are identified pursuant to 37 CFR
§§ 1.56, 1.97, and 1.98. Copies of the patents are included as required.

Entry and consideration of the submitted documents are solicited.

Respectfully submitted,

MARSHALL, GERSTEIN & BORUN LLP

By:

James P. Zeller
Reg. No. 28,491
Attorneys for Applicants

March 21, 2005

6300 Sears Tower
233 South Wacker Drive
Chicago, Illinois 60606-6357
(312) 474-6300

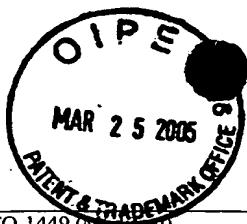


Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Atty. Docket No. 30848/40704	Serial No. 10/516,384
		Applicant Gogolides et al.	
		Filing Date May 30, 2003	Group

U.S. PATENT DOCUMENTS

*Examiner Initials	Document Number	Issue Date	Name	Class	Subclass	Filing Date if Appropriate
	2001/0018486A1	08/30/01	Lichtenhan et al.	524	588	
	6,391,471 B1	05/21/02	Hiraoka et al.	428	623	
	2003/0022102 A1	01/30/03	Hiraoka et al.	430	270.1	03/07/02

FOREIGN PATENT DOCUMENTS



Form PTO-1449 (Medium)	U.S. Department of Commerce Patent and Trademark Office	Atty. Docket No. 30848/40704	Serial No. 10/516,384
INFORMATION DISCLOSURE STATEMENT		Applicant Gogolides et al.	
		Filing Date May 30, 2003	Group

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)	
	"Double Layer Resist System for High Resolution Lithography", Hatzakis et al., Proc. Microcircuit Engnrg. Lausanne, 1981, pp. 386-396
	"Linear Hybrid Polymer Building Blocks: Methacrylate-Functionalized Polyhedral Oligomeric Silsesquioxane Monomers and Polymers", Lichtenhan et al., Macromolecules 28, 1995, pp. 8435-8437
	"Extension of 248 nm Optical Lithography: A Thin Film Imaging Approach", Lin et al., SPIE Vol. 3333, 1998, pp. 278-288
	"Outlook for 157-nm Resist Design", Kunz et al., SPIE Vol. 3678, March 1999, pp. 13-20
	"Incorporation of Polyhedral Oligosilsesquioxane in Chemically Amplified Resists to Improve Their Reactive Ion Etching Resistance", Wu et al., J. Vac. Sci. Technol. B 19(3), May/June 2001, pp. 851-855
	"Novel CA Resists with Photoacid Generator in Polymer Chain", Wu et al., SPIE Vol. 4345, 2001, pp. 521-527
	"Novel Positive-Tone Chemically Amplified Resists with Photoacid Generator in the Polymer Chains", Wu et al., Adv. Mater 13, No. 9, May 2001, pp. 670-672
	"Silicon-Containing Resists for 157 nm Applications", Sooriyakumaran et al., SPIE Vol. 4345, 2001, pp. 319-326
	"Recent Advances in Resists for 157 nm Microlithography", Trinque et al., J. Vac. Sci. Technol. B 20(2), March/April 2002, pp. 531-536
	International Search Report in PCT/GB03/00018 dated September 23, 2003

Examiner	Date Considered
----------	-----------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.